

POLISHING PAD AND METHOD FOR PRODUCING POLISHING PAD

Abstract

Provided are a method for producing a finish polishing pad and the polishing pad which allow formation of a stable film and enables polishing with fewer polishing scratches. The method is a method for producing a polishing pad comprising a film substrate and a polyurethane resin film as a polishing layer on the film substrate, the method comprising the steps of: dissolving a composition for forming polyurethane resin film containing a polyurethane resin and an additive(s) in a solvent capable of dissolving the resin; removing an insoluble component(s) to make the content of the insoluble component(s) in the solution less than 1% by mass relative to the total mass of the composition for forming polyurethane resin film; adding a poor solvent to the solution from which the insoluble component(s) has(have) been removed, followed by mixing, the amount (ml) of the poor solvent added per gram of the solid content mass of the resin being calculated according to Formula 1: the amount (ml) = a coagulation value (ml) of the polyurethane resin determined by using the poor solvent $\times$ A (A = 0.007 to 0.027); and forming a film from the mixture solution on the film formation substrate by a wet coagulation method, to thereby form the polyurethane resin film.

Fig. 1(a) and (b)